

CLAIMS:

1. System for reducing oxidation of a semiconductor device comprising:
a holding device for securing the semiconductor device to a platform,
5 including an opening in the holding device for providing access to an area
where the semiconductor device is to be heated;
a cavity coupled to the opening; and
a gas inlet in fluid communication with the cavity for supplying a
relatively inert gas to the cavity, whereby to transmit the inert gas to the
10 opening through the cavity.
2. System as claimed in claim 1, wherein the cavity is configured such
that the inert gas supplied to the cavity is directed away from an outlet
connecting the cavity to the opening.
15
3. System as claimed in claim 1, including a conduit between the cavity
and gas inlet for diverting the inert gas into the cavity.
4. System as claimed in claim 2, wherein the conduit is formed in the
20 holding device.
5. System as claimed in claim 1, wherein the cavity is formed in the
holding device.
- 25 6. System as claimed in claim 1, wherein the gas inlet is formed in the
holding device.
7. System as claimed in claim 1, wherein the gas inlet is formed in the
platform.
30
8. System as claimed in claim 1, including a space between the holding
device and the platform for receiving the inert gas from the gas inlet and for
distributing the inert gas over a surface of the electronic device.

9. System as claimed in claim 8, wherein the space is connected to the said opening for distributing an amount of the inert gas directly from the space to the opening.
- 5 10. System as claimed in claim 8, including a conduit linking the cavity and the space for channeling an amount of the inert gas from the space to the cavity.
11. Method for reducing oxidation of a semiconductor device comprising
10 the steps of:
 securing the semiconductor device to a platform with a holding device including an opening;
 positioning the opening of the holding device over an area of the semiconductor device where it is to be heated for providing access thereto;
15 providing a cavity coupled to the opening;
 supplying a relatively inert gas into the cavity; and
 transmitting the inert gas to the opening through the cavity.
12. Method as claimed in claim 11, including directing the inert gas
20 supplied to the cavity away from an outlet connecting the cavity to the opening.
13. Method as claimed in claim 11, including diverting the inert gas into the cavity through a conduit linking the cavity to the supply of inert gas.
25
14. Method as claimed in claim 11, including supplying the inert gas into a space between the holding device and the platform and distributing the inert gas over a surface of the electronic device.
- 30 15. Method as claimed in claim 14, including distributing an amount of the inert gas directly from the space to the opening of the holding device.

16. Method as claimed in claim 14, including channeling inert gas from the space to the cavity, whereby to transmit the inert gas to the said opening through the cavity.